

## NLP 2000 System

### Introduction

NanoInk's NLP 2000 System is a user-friendly and easy to operate desktop nanolithography instrument capable of depositing a wide variety of materials with sub-micron accuracy and precision. Using NanoInk's proprietary MEMS devices and deposition protocols with the NLP 2000 System's printing and automation software, users can create custom patterned substrates in under an hour.

### Applications

The NLP 2000 System is ideal for nanoengineering and biomaterials applications which require 1-10 micron printing and imaging capabilities, such as:

- Multiplexed protein printing
- Biosensor functionalization
- Cell micro and nanopatterning studies
- Polymer patterning, including ethylene glycol and acrylic

### Standard Components

- NLP 2000 System stage, optics, and controller
- M-type Multipen Arrays, InkWells, and substrates
- On-site system installation
- Two days user training
- Getting Started Guide, User Manual & CD
- 1 year warranty, parts & labor

### Optional Components

- Localized environmental chamber (EC-0110-00)
- Integrated vibration isolation feet (ATB-0100-00)
- 2D nano PrintArray™ upgrade (NLP-0100-01)
- 1D leveling & scripting (NLP-0400-01)
- 1D & 2D leveling & scripting (NLP-0500-01)
- Plasma cleaner (DPN-0312-01/02)
- Active Vibration Isolation Table (ATB-0200-00)
- Extended Limited Warranty, 1 year (NLP-0310-01)

### Features and Benefits

Along with the ability to create patterns of nano- to micron-scale features from many materials, benefits of the NLP 2000 System include:

- Rapid fabrication of multi-component patterns with 1-10 micron feature sizes



Figure 1: NLP 2000 System.

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- Automated, precise, co-planar patterning of areas as large as 40 mm x 40 mm
- Functionalization of pre-existing microstructures
- Process monitoring & control using high resolution optical microscopy & environmental chamber

## Rapid Fabrication of Multicomponent Patterns

Many researchers (including those studying cell-substrate interactions, developing sensors, and analyzing proteins) need to rapidly pattern materials with features in the 1-10 micron size range. The NLP 2000 System is the only commercially available platform capable of patterning 1-10 micron features of multiple materials with sub-micron registry. With the NLP 2000 System's user-friendly software and materials deposition protocols, it is simple to go from idea to final product in less than an hour.

## Automated, Precise Patterning of Large Areas

In addition to a large 40 mm x 40 mm XY stage, The NLP 2000 System includes everything needed for users to begin to rapidly pattern large surface areas after only minimal training. The NLP 2000's three encoded piezo-driven linear stages (XYZ) and 2 encoded goniometer stages ( $T_x$  and  $T_y$ ) make precise, rapid, large area patterning repeatable. Automated leveling controls, standard patterning routines, and software scripting capabilities simplify, control and automate long deposition runs.

## Microstructure Functionalization

Using the NLP 2000 System's high resolution stages, sub-micron optical resolution and simple patterning interface, scientists can easily functionalize sensors, sensor arrays, microcontact printing stamps, microfluidic devices, or other pre-fabricated microstructures. The NLP 2000 System easily resolves features less than a micron in size, enabling system alignment to these pre-fabricated microstructures.

## Controlled Patterning Environment

To fully monitor & control the patterning process, the NLP 2000 System features a high resolution optical microscope, and environmental chamber, and vibration isolation. Integrated environmental controls allow the user control and log temperature, humidity, and other unit parameters for immediate or subsequent analysis and correlation with printing. In addition, the NLP 2000 is compatible with commercial passive and active vibration isolation tables.

## System Specifications

### High Resolution Stage Specifications

|                                      | X-Axis       | Y-Axis       | Z -Axis     | $T_x$           | $T_y$           |
|--------------------------------------|--------------|--------------|-------------|-----------------|-----------------|
| Range                                | 40 mm        | 40 mm        | 10 mm       | $\pm 5^\circ$   | $\pm 5^\circ$   |
| Encoder resolution                   | 5 nm         | 5 nm         | 5 nm        | 0.15 mDeg       | 0.15 mDeg       |
| Stage repeatability (High Res. Mode) | $\pm 25$ nm  | $\pm 25$ nm  | $\pm 75$ nm | $\pm 0.25$ mDeg | $\pm 0.25$ mDeg |
| Stage repeatability (Low Res. Mode)  | $\pm 150$ nm | $\pm 150$ nm | $\pm 75$ nm | $\pm 0.25$ mDeg | $\pm 0.25$ mDeg |

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## Patterning Specifications

|   |  |            |                                   |                 |                                   |                 |                     |    |    |     |       |                     |    |    |     |       |
|---|--|------------|-----------------------------------|-----------------|-----------------------------------|-----------------|---------------------|----|----|-----|-------|---------------------|----|----|-----|-------|
| Throughput                                | System throughput is application-dependant; typical examples for printing an array of 2 micron protein spots spaced 10 microns apart with various multi-“pen” tip arrays, assuming re-inking every 10 spots: <table><tr><td>“Pen” Type</td><td>“Pen” Tips/ Array</td><td>Time (min)</td><td>Patterned Area (mm<sup>2</sup>)</td><td>Number of Spots</td></tr><tr><td>12 pen M-type array</td><td>12</td><td>30</td><td>0.1</td><td>1,000</td></tr><tr><td>48 pen M-type array</td><td>48</td><td>30</td><td>0.4</td><td>4,000</td></tr></table> Automated re-inking of multiple pen arrays | “Pen” Type | “Pen” Tips/ Array                 | Time (min)      | Patterned Area (mm <sup>2</sup> ) | Number of Spots | 12 pen M-type array | 12 | 30 | 0.1 | 1,000 | 48 pen M-type array | 48 | 30 | 0.4 | 4,000 |
| “Pen” Type                                | “Pen” Tips/ Array  | Time (min) | Patterned Area (mm <sup>2</sup> ) | Number of Spots |                                   |                 |                     |    |    |     |       |                     |    |    |     |       |
| 12 pen M-type array                       | 12   | 30         | 0.1                               | 1,000           |                                   |                 |                     |    |    |     |       |                     |    |    |     |       |
| 48 pen M-type array                       | 48   | 30         | 0.4                               | 4,000           |                                   |                 |                     |    |    |     |       |                     |    |    |     |       |
| Feature size                              | 250 nm - 10 microns  |            |                                   |                 |                                   |                 |                     |    |    |     |       |                     |    |    |     |       |
| Coefficient of variation                  | 5-20% consistency (depends on printing material & protocol optimization)   |            |                                   |                 |                                   |                 |                     |    |    |     |       |                     |    |    |     |       |
| Leveling                                  | Stage leveling wizard (standard); automated leveling (1D & 2D) optional  |            |                                   |                 |                                   |                 |                     |    |    |     |       |                     |    |    |     |       |
| Optical pattern registration to substrate | 1 micron   |            |                                   |                 |                                   |                 |                     |    |    |     |       |                     |    |    |     |       |

## Imaging & Environmental Control Specifications

|  |  |
|--|--|
| Optical imaging specifications             | 10x objective M plan APO<br>Optical resolution: < 1 $\mu$ m<br>Motorized digitally controlled zoom and focus<br>Digitally controlled halogen illumination system<br>0% zoom: 844 $\mu$ m x 629 $\mu$ m<br>100% zoom: 143 $\mu$ m x 110 $\mu$ m<br>Video magnification: (280x -1700x) |
| Localized environmental control (optional) | Software controlled temperature & humidity<br>Heating temperature range: (ambient + 20°C)<br>Cooling temperature range: (ambient – 2°C)<br>Temperature stability: +/- 0.5 °C<br>Humidity range: (10-90% RH)<br>Humidity stability: +/- 5% RH   |

## Software Specifications

|                                    |   |
|------------------------------------|---|
| Pattern Design                     | Patterning of orthogonal dots and lines<br>Arrays of dots and lines<br>InkMap import of Bitmaps<br>User controlled pattern sequencing<br>Pattern preview window<br>InkMap for import of bitmap patterns |
| Feature Size Control               | User defined dot dwell time; user defined line patterning speed   |
| Stage Movement                     | XYZ increments preset or user-defined<br>Tip & Tilt increments preset or user defined<br>Ability to capture and store X, Y, Z, Tx and Ty stage positions<br>Tip approach                                |
| Pen Array/Sample Leveling Routines | Leveling uses 3 point capture to optically define the substrate surface plane   |

## Consumables, Printing Materials and Substrates

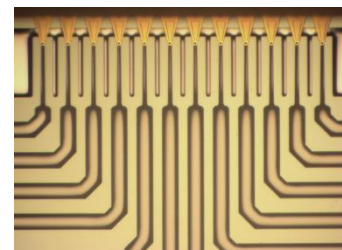
### Multi-pen Arrays & Inkwells

Arrays of “pen” tips are optimized for DPN deposition of one or more printing materials in large-area patterns. “Pen” tip arrays are made of silicon nitride and contain A-frame and diving board shaped cantilevers. “Pen” tips are loaded using NanoInk Inkwell reservoirs.

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| Pen Type                | Pen Tips/Array  | Compatible Inkwells |
|-------------------------|-----------------|---------------------|
| C                       | 10              | Universal           |
| D                       | 24              | Universal           |
| F                       | 50              | Universal           |
| E                       | 18              | Universal           |
| M                       | 12              | M12                 |
| 48 Bio M                | 48              | 48 Bio M            |
| 2DnPA                   | 55,000          | --                  |
| High Density Tip Arrays | 10 <sup>6</sup> | --                  |



**Figure 2:** Type M 12-pen array dipping into matching inkwell array.

## Printing Materials & Substrates

The NLP 2000 System is capable of depositing and imaging molecular materials and liquids with viscosities ranging from 1-20,000 cP on NanoInk substrates.

Supported printing materials:

- Proteins
- Nucleic acids
- Lipids
- Nanoparticles
- Polyethylene glycol
- UV-curable polymers
- Heat-curable polymers
- Glycerol
- Silanes
- Thiols
- Catalysts

Compatible substrates:

- Silicon
- Silicon dioxide
- Silanized surfaces
- Amine functionalized slides
- Metals
- PDMS
- Hydrogels
- Polystyrene

## Proven Protocols and Support

Leveraging years of experience and expertise in nanolithographic techniques and applications, NanoInk is committed to developing and thoroughly testing deposition protocols for a multitude of scientifically important materials (including DNA, hydrogels, polymers, silanes, thiols, and nanoparticles). These protocols, and accompanying inks, substrates and pens, are made available to NLP 2000 customers, and are accompanied by a variety of levels of customer support including e-mail, phone, remote desktop, on-site, and forums.

## Ordering Information

Item Name: System, NLP 2000

Part #: DPN-1502-01

Learn more about NanoInk products and services at [www.nanoink.net](http://www.nanoink.net). Or call us at 847-679-NANO (6266).